

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

FIRST INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

In accordance with the duty of disclosure as set forth in 37 C.F.R. § 1.56, the accompanying information is being submitted in accordance with 37 C.F.R. §§ 1.97 and 1.98.

All of the listed documents were previously made of record in prior Application Serial No. 10/043,190, now U.S. Patent No. 6,758,224, filed January 14, 2002, upon which Applicants rely for the benefits provided in 35 U.S.C. § 120.

The documents are being submitted after a first Office Action on the merits but prior to the closing of prosecution, therefore under 37 C.F.R. § 1.97(c), the fee set forth in 37 C.F.R. § 1.17(p) is enclosed.

A fee of \$180.00 (1806) as set forth in 37 C.F.R. § 1.17(p) is enclosed.

FIRST Information Disclosure Statement
Application No. 10/709,622
Attorney's Docket No. 001425-126
Page 2

To assist the Examiner, the documents are listed on the attached form PTO-1449. It is respectfully requested that an Examiner initialed copy of this form be returned to the undersigned.

Respectfully submitted,

BURNS, DOANE, SWECKER & MATHIS, L.L.P.

Date 3-2-05

y: **www**

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FIRST INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Substitute for form 1449A/PTO & 1449B/PTO

6,538,734

Sheet

Complete if Known				
Application Number	10/709,622			
Filing Date May 18, 2004				
First Named Inventor	Hiroshi Nogami			
Examiner Name	JEFFRIE ROBERT LUND			
Attorney Docket Number	001425-126			

	MAR 0	र याम हैं।	U.S. PATENT DOCUMENTS	
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Signature Considered	

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as many sheets as necessary)

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Attorney Docket Number	001425-126			

NON-PATENT LITERATURE DOCUMENTS Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, Examiner Initials serial symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. Shing PADOMURA et al., "ANISOTROPIC ETCHING USING DEPOSITION OF SULFUR, Sony Corporation, Semiconductor World, January 1993, pp. 1-11, and translation Ken FUJITA et al., "X-RAY PHOTOELECTRON SPECTROSCOPIC STUDIES ON PYROLYSIS OF PLASMA-POLYMERIZED FLUOROCARBON FILMS ON SI", Jpn. J. Appl. Phys. volume 34 (1995), pp. 304-306, Part 1, NO. 1, January 1995 Robert C. REID et al., "THE PROPERTIES OF GASES AND LIQUIDS", McGraw-Hill, Inc., Appendix B, Index R. Byron BIRD et al., "TRANSPORT PHENOMENA", Jon Wiley & Sons, pp. 508-509 and 512-513 Riccardo d'AGOSTINO et al., "PLASMA ETCHING OF Si and SiO₂ in SF₆-O₂ MIXTURES", J. Appl. Phys. 52(1), January 1981, pp. 162-167 Robert C. REID et al. "Lennard-Jones Potentials as Determined from Viscosity Data (Appendix B)". The Properties of Gases and Liquids, McGraw-Hill, Inc., Copyright 1987, p.734, Index R. Byron BIRD et al. "Diffusivity and the Mechanisms of Mass Transport; Theory of Ordinary Diffusion in Gases at Low Density", *Transport Phenomena*, John Wiley & Sons, Inc., Copyright 1960, p. 508-513 A new technique for diagnostics of a radio-frequency parallel-plate remote plasma; N. Sano et al.; Appl. Phys. Lett 65 (2), 11 July 1994 pages 162-164. Infrared spectroscopic study of SiO, films produced by plasma enhanced chemical vapor deposition; J. Vac.Sci. Technol. A4(3), May/June 1986; pages 689-694. Improvement of structural and electrical properties in low-temperature gate oxides for poly-Si TFTs by controlling O₂/Sih₄ ratios; AM-LCD 1997; pages 87-90. "Flow of Atoms and Molecules—Rarefied Gas Dynamics and its Applications", section 2.6.4, The Japan

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